

AMENDMENTS TO THE CLAIMS

1-18. (canceled)

19. (original) A gas delivery system for a deposition chamber, comprising:
a first line coupleable to a first source chemical, wherein the first line communicates with a plurality of first holes in communication with the chamber; and
a second line coupleable to a second source chemical, wherein the second line communicates with a plurality of second holes in communication with the chamber.

20. (original) The gas delivery system of claim 19, further comprising:
first flow regulators proximate to each of the first holes for controlling the flow of the first source chemical to the chamber; and
second flow regulators proximate to each of the second holes for controlling the flow of the second source chemical to the chamber.

21. (original) The gas delivery system of claim 20, wherein either the first or second flow regulators comprises a device selected from the group consisting of a valve, pump, or flow controller.

22. (original) The gas delivery system of claim 20, further comprising a shower head for housing the first and second flow regulators devices and the first and second lines.

23. (original) The gas delivery system of claim 19, wherein the first and second holes are located in an area on the chamber, and wherein the first and second holes are evenly distributed about the area.

24. (original) The gas delivery system of claim 23, further comprising a shower head, and wherein the area is located on the shower head.

25. (original) The gas delivery system of claim 20, wherein either the first or second flow regulators are capable of vaporizing either the first or second source chemicals.

26. (original) The gas delivery system of claim 20, further comprising a controller coupled to the first and second flow regulators for controlling the flow of the first and second source chemicals to the chamber.

27. (original) The gas delivery system of claim 26, wherein the controller is capable of controlling each of the first and second flow regulators independently.

28. (original) The gas delivery system of claim 26, wherein the controller is capable of controlling the first flow regulators in unison, and is capable of controlling the second flow regulators in unison.

29. (original) A deposition system, comprising:
a deposition chamber containing a support for holding a substrate onto which a film is to be deposited;
a first source chemical coupled by a first line to a plurality of first holes in communication with the chamber; and
a second source chemical coupled by a second line to a plurality of second holes in communication with the chamber.

30. (original) The deposition system of claim 29, further comprising:
first flow regulators proximate to each of the first holes for controlling the flow of the first source chemical to the chamber; and
second flow regulators proximate to each of the second holes for controlling the flow of the second source chemical to the chamber.

31. (original) The deposition system of claim 30, wherein either the first or second flow regulators comprises a device selected from the group consisting of a valve, pump, or flow controller.

32. (original) The deposition system of claim 30, further comprising a shower head for housing the first and second flow regulators devices and the first and second lines.

33. (original) The deposition system of claim 30, wherein the first and second holes are located in an area on the chamber, and wherein the first and second holes are evenly distributed about the area.

34. (original) The deposition system of claim 33, further comprising a shower head, and wherein the area is located on the shower head.

35. (original) The deposition system of claim 30, wherein either the first or second flow regulators are capable of vaporizing either the first or second source chemicals.

36. (original) The deposition system of claim 30, further comprising a controller coupled to the first and second flow regulators for controlling the flow of the first and second source chemicals to the chamber.

37. (original) The deposition system of claim 36, wherein the controller is capable of controlling each of the first and second flow regulators independently.

38. (original) The deposition system of claim 36, wherein the controller is capable of controlling the first flow regulators in unison, and is capable of controlling the second flow regulators in unison.

39-64. (canceled)